AMENDMENTS TO THE CLAIMS:

1. (Currently Amended) ~~A nano-imprint system~~ An apparatus for monitoring mold deformation in nano-imprint, comprising:

a mold ~~comprising a~~ body having a first surface and an opposite second surface, imprinting patterns being formed in areas of the second surface;

an electrostatic plate capacitor comprising first and second metal film electrodes respectively embedded in the first and second surfaces of the mold body and spaced a distance from each other and a metal lead embedded in the mold body and connecting the first and second metal film electrodes;

a detection device detecting a capacitance of the electrostatic plate capacitor and comprising means for converting the capacitance into an amount of deformation of the mold body; and

an external monitoring device receiving a signal representing the amount of deformation from the detection device and selectively recording and displaying the amount of deformation and comprising means for comparing the amount of deformation with a reference to determine if the amount of deformation exceeds the reference and selectively issuing a warning and shutting down the system.

2. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 1, wherein the imprinting patterns of the mold body selectively comprise micro-scale patterns and nano-scale patterns.

3. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 1, wherein the metal

film electrodes are formed on the mold body without overlapping the imprinting patterns.

4. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 1, wherein the electrostatic plate capacitor and the detection device [[is]] are coupled to the external monitoring device by a cable.

5. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 1, wherein the electrostatic plate capacitor and the detection device [[is]] are coupled to the external monitoring device in a wireless manner.

6. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 5, wherein the wireless coupling comprises a wireless transmitter that receives and encodes the detection result from the detection device and transmits a wireless signal and a wireless receiver that receives the wireless signal and a decoder that decodes the received wireless signal and applies a corresponding signal to the external monitoring device.

7. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 1, wherein the detection device comprises a detection circuit for detecting the capacitance of the electrostatic plate capacitor and issues a detection signal, a modulation circuit for modulating the detection signal and issuing a modulated signal, an analog-to-digital converter that receives and converts the modulated signal into a digital signal, and a signal processing circuit that processes ~~process~~ and converts the digital signal into the amount of deformation of the mold body.

8. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 7, wherein the detection circuit, the modulation circuit, the analog-to-digital converter and the signal processing circuit are coupled by physical electrical connections.

9. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 7, wherein the detection circuit, the modulation circuit, the analog-to-digital converter and the signal processing circuit are coupled by wireless connections.

10. (Currently Amended) The apparatus ~~system~~ as claimed in Claim 9, wherein the wireless coupling comprises a wireless transmitter that receives and encodes a first signal and transmits a wireless signal and a wireless receiver that receives the wireless signal and a decoder that decodes the received wireless signal and issues a corresponding second signal.

11. (Currently Amended) A method for monitoring amount of deformation of a nano-imprint mold comprising the following steps:

~~(A)~~ (1) detecting and recording a reference capacitance of an electrostatic plate capacitor embedded in the nano-imprint mold at a first time point before the start of an imprinting process carried out with the nano-imprint mold;

~~(B)~~ (2) detecting a capacitance of the electrostatic plate capacitor at a second time point after the imprinting process is being carried out;

~~(C)~~ (3) processing the capacitance detected at the second time point to obtain an amount of deformation of the nano-imprint mold;

~~(D)~~ (4) feeding the amount of deformation to an external monitoring device and

recording the amount of the deformation;

~~(E)~~ (5) using the external monitoring device to display and selectively determine if the amount of deformation exceeds a limit that is determined on the basis of the reference capacitance; and

~~(F)~~ (6) if the amount of deformation exceeds the limit, then selectively issuing warning and selectively stopping the imprinting process otherwise repeating steps (2)-(5).

12. (Original) The method as claimed in Claim 11, wherein in step (2), the capacitance of the electrostatic plate capacitor is detected by a detection circuit.

13. (Currently Amended) The method as claimed in Claim 11, wherein in step (3), the capacitance is detected by a circuit and represented as an electrical signal and wherein step (3) further comprises the following sub-steps:

(A) modulating the signal representing the capacitance to issue a modulated signal;

(B) converting the modulated signal into a digital signal; and

(C) comparing the digital signal with the reference capacitance and calculating the amount of [[the]] deformation.

14. (Original) The method as claimed in Claim 11, wherein in step (5), the amount of deformation is directly displayed on a display device of the external monitoring device.